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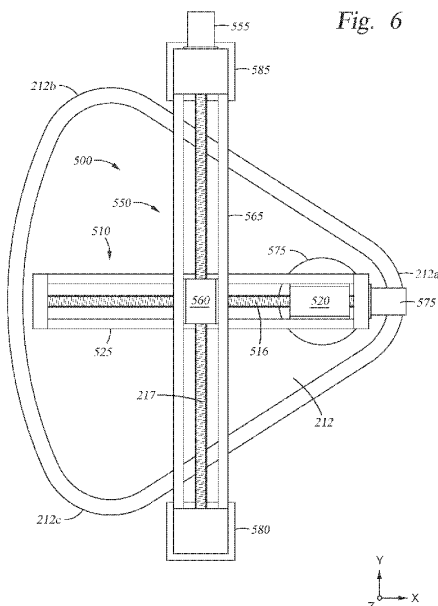
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- (54) **Title: PHYSICAL VAPOR DEPOSITION SOURCE AND CHAMBER ASSEMBLY**



(57) **Abstract:** Apparatus and methods for improving film uniformity in a physical vapor deposition (PVD) process are provided herein, in some embodiments, a magnetron translation assembly comprises a first linear actuator assembly with a first rail which is aligned in a first direction and a first actuator that is configured to position a first mount along the first rail; a magnet assembly is mounted on the first mount, the magnet assembly constructed and arranged to be rotated about an axis perpendicular to the first rail; and a second linear actuator assembly comprising a second mount that is configured to be positioned along a second rail, which is aligned in a second direction and the first linear actuator assembly is coupled to a mounting surface of the second mount.

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